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HTPD 2018



Contribution ID: 408 Type: not specified

6.29 Thomson scattering systems on C-2W field-reversed configuration plasma experiment

Tuesday, 17 April 2018 10:31 (120)

TAE Technologies' newly constructed C-2W experiment aims to improve the ion and electron temperature (Te) in a sustained field-reversed-configuration (FRC) plasma. A suite of Thomson scattering systems has been designed and constructed for electron temperature and density (ne) profile measurement. The systems are designed for electron density and temperature ranges of $1\times10(12)$ cm(-3) to $2\times10(14)$ cm(-3) and 10eV to 2keV. The central system will provide profile measurement of Te/ne at 16 radial locations from r=-9cm to r=64cm with a temporal resolution of 20kHz/4 pulses or 1kHz/30 pulses. The jet system will provide profile measurement of Te/ne at 5 radial locations in the open field region from r=-5cm to r=15cm with a temporal resolution of 100Hz. The systems and their components have been characterized and calibrated [1,2]. A maximum-likelihood algorithm has been applied for data processing and analysis. [1] T. Schindler Calibrations of Thomson Scattering Diagnostic on C-2W HTPD 2018 [2] A. Ottaviano Characterization of System Components for Thomson Scattering Diagnostics on C-2W HTPD 2018

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Session Classification: Session #6, Tuesday Morning Poster Session